

PROCEEDINGS OF SPIE

Optical Technology and Measurement for Industrial Applications 2020

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Editors

**Yokohama, Japan
20–24 April 2020**

Sponsored by
The Japan Society for Precision Engineering (JSPE)
SPIE

Published by
SPIE

Volume 11523

Proceedings of SPIE 0277-786X, V. 11523

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Optical Technology and Measurement for Industrial Applications 2020, edited by T. Hatsuzawa, R. Tutsch, T. Yoshizawa,
Proc. of SPIE Vol. 11523, 1152301 · © 2020 SPIE · CCC code: 0277-786X/20/\$21 · doi: 10.1117/12.2574753

Proc. of SPIE Vol. 11523 1152301-1

The papers in this volume were part of the technical conference cited on the cover and title page. Papers were selected and subject to review by the editors and conference program committee. Some conference presentations may not be available for publication. Additional papers and presentation recordings may be available online in the SPIE Digital Library at SPIEDigitalLibrary.org.

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Please use the following format to cite material from these proceedings:

Author(s), "Title of Paper," in *Optical Technology and Measurement for Industrial Applications 2020*, edited by Takeshi Hatuszawa, Rainer Tutsch, Toru Yoshizawa, Proceedings of SPIE Vol. 11523 (SPIE, Bellingham, WA, 2020) Seven-digit Article CID Number.

ISSN: 0277-786X

ISSN: 1996-756X (electronic)

ISBN: 9781510638532

ISBN: 9781510638549 (electronic)

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

SPIE.org

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Introduction

The first Optical Technology and Measurement for Industrial Applications Conference (OPTM) was held in Minatomirai, Yokohama JAPAN from 23 to 25 April 2019, as a part of the Optics and Photonics International Congress 2019, sponsored by the SPIE and Mechano-optics technical committee in the Japan Society of Precision Engineering. In the conference, 35 oral presentations and 15 posters were presented, which quite a lot for a first time. The topics are full of variety ranging from profilometry, data acquisition, metrology, inspection etc., showing deep interests in this technical field.

The aim of the OPTM 2020 is to provide an international opportunity for introducing up-to-date technology in the field of optical measurement and their applications for industries while at the same time, providing a networking opportunity for young researchers and students; which is another important role of the conference. Also in the venue, other optics related exhibitions and conferences will be held which is a good chance to foster interest in different technical fields. We hope your visit to the port of Yokohama will represent a new step in your technical and research career.

**Takeshi Hatsuzawa
Rainer Tutsch
Toru Yoshizawa**

